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Entry 40 of 40

File: DWPI

Sep 10, 1974

DERWENT-ACC-NO: 1975-55155W

DERWENT-WEEK: 197533

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TITLE: Platinum coatings deposition - by high temp. dissociation of  
organo-platin um cpds

PATENT-ASSIGNEE: GORKI UNIV CHEM RES[UYGOR]

## PRIORITY-DATA:

1973SU-1874554

February 5, 1973

## PATENT-FAMILY:

PUB-NO

PUB-DATE

LANGUAGE

PAGES

MAIN-IPC

SU 441359 A

September 10, 1974

N/A

000

N/A

INT-CL (IPC): C23C 11/02

ABSTRACTED-PUB-NO: SU 441359A

## BASIC-ABSTRACT:

The Pt coatings are formed on heated substrates by dissociating acetylacetonate-trimethyl-platinum. The reaction chamber is evacuated to a pressure of 1-15 mm. Hg and the evaporator is filled with 0.325 g. of the above organo-platinum cpd. The degreased substrate is heated to 250 degrees C. (in the case of teflon) or 250 degrees C. (in the case of steel. The proposed process ensures very low carbon content in the Pt coating and increases the thickness of the coating. The Pt coatings have very good adhesion to the substrate.

## TITLE-TERMS:

PLATINUM COATING DEPOSIT HIGH TEMPERATURE DISSOCIATE ORGANO PLATINUM COMPOUND

DERWENT-CLASS: M13

CPI-CODES: M13-E01;

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(FILE 'HOME' ENTERED AT 09:09:20 ON 27 OCT 1999)

FILE 'CAPLUS' ENTERED AT 09:09:27 ON 27 OCT 1999

L1 101 S TRIMETHYL(3W) (PLATINUM OR PT)  
L2 10 S L1 AND VAPOR

FILE 'JAPIO' ENTERED AT 09:13:52 ON 27 OCT 1999

L3 1 S L1

=> d 12 1-10

YOU HAVE REQUESTED DATA FROM FILE 'CAPLUS' - CONTINUE? (Y)/N:y

L2 ANSWER 1 OF 10 CAPLUS COPYRIGHT 1999 ACS

AN 1999:468094 CAPLUS

DN 131:88052

TI **Trimethyl**(ethylcyclopentadienyl)**platinum**, process for  
producing the same and process for producing platinum-containing films  
with the use of the same

IN Kadokura, Hidekimi

PA Kabushikikaisha Kojundokagaku Kenkyusho, Japan

SO U.S., 4 pp.

CODEN: USXXAM

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
	-----	---	-----	-----	-----
PI	US 5929267	A	19990727	US 1999-251752	19990217
	JP 11292889	A2	19991026	JP 1998-129406	19980403
PRAI	JP 1998-129406	19980403			

L2 ANSWER 2 OF 10 CAPLUS COPYRIGHT 1999 ACS

AN 1999:14342 CAPLUS

DN 130:244581

TI Comparison of beam-induced deposition using ion microprobe

AU Park, Y. K.; Nagai, T.; Takai, M.; Lehrer, C.; Frey, L.; Ryssel, H.

CS Research Center for Materials Science at Extreme Conditions, Osaka  
University, Toyonaka, Osaka, 560-8531, Japan

SO Nucl. Instrum. Methods Phys. Res., Sect. B (1999), 148(1-4), 25-31

CODEN: NIMBEU; ISSN: 0168-583X

PB Elsevier Science B.V.

DT Journal

LA English

L2 ANSWER 3 OF 10 CAPLUS COPYRIGHT 1999 ACS

AN 1998:641760 CAPLUS

DN 130:9301

TI The usage of focused ion beam induced deposition of gold film in IC  
device

modification and repair

AU Lee, R.; Cecere, M.

CS Schlumberger ATE, San Jose, CA, 95110, USA

SO ISTFA '97, Proc. Int. Symp. Test. Failure Anal., 23rd (1997), 121-123

Publisher: ASM International, Materials Park, Ohio.

CODEN: 66TPAK

DT Conference

LA English

L2 ANSWER 4 OF 10 CAPLUS COPYRIGHT 1999 ACS

AN 1998:215531 CAPLUS

DN 128:302882

TI Fabrication of field emitter array using focused ion and electron beam induced reaction

AU Takai, M.; Kishimoto, T.; Morimoto, H.; park, Y. K.; Lipp, S.; Lehrer, C.;

Frey, L.; Ryssel, H.; Hosono, A.; Kawabuchi, S.

CS Research Center Materials Science Extreme Conditions, Osaka University, Osaka, 560, Japan

SO Microelectron. Eng. (1998), 41/42, 453-456

CODEN: MIENEF; ISSN: 0167-9317

PB Elsevier Science B.V.

DT Journal

LA English

L2 ANSWER 5 OF 10 CAPLUS COPYRIGHT 1999 ACS

AN 1996:111174 CAPLUS

DN 124:207027

TI MOPECVD of thin platinum films

AU Basner, R.; Ledjeff, K.; Schmidt, M.; Zylka, D.

CS Institut fur Niedertemperatur-Plasmaphysik, Greifswald, 0-2200, Germany

SO Acta Phys. Univ. Comenianae (1993), Volume Date 1993, 34(2), 173-84

CODEN: APUCED; ISSN: 0231-889X

DT Journal

LA English

L2 ANSWER 6 OF 10 CAPLUS COPYRIGHT 1999 ACS

AN 1994:512165 CAPLUS

DN 121:112165

TI manufacture of electrochemical gas sensors

IN Yamaga, Noryuki; Hatai, Takashi; Kusanagi, Shigekazu

PA Matsushita Electric Works Ltd, Japan

SO Jpn. Kokai Tokkyo Koho, 5 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
	-----	----	-----	-----	-----
PI	JP 06160349	A2	19940607	JP 1992-313834	19921125

L2 ANSWER 7 OF 10 CAPLUS COPYRIGHT 1999 ACS

AN 1990:441002 CAPLUS

DN 113:41002

TI Characterization of (methylcyclopentadienyl)trimethylplatinum and low-temperature organometallic chemical **vapor** deposition of platinum metal [Erratum to document cited in CA111(25):233169n]

AU Xue, Ziling; Strouse, M. Jane; Shuh, David K.; Knobler, Carolyn B.;

Kaeszt,

Herbert D.; Hicks, Robert F.; Williams, R. Stanley

CS Dep. Chem. Biochem., Univ. California, Los Angeles, CA, 90024-1569, USA

SO J. Am. Chem. Soc. (1990), 112(10), 4090

CODEN: JACSAT; ISSN: 0002-7863

DT Journal

LA English

L2 ANSWER 8 OF 10 CAPLUS COPYRIGHT 1999 ACS

AN 1989:633169 CAPLUS

DN 111:233169

TI Characterization of (methylcyclopentadienyl)trimethylplatinum and  
low-temperature organometallic chemical **vapor** deposition of  
platinum metal

AU Xue, Ziling; Strouse, M. Jane; Shuh, David K.; Knobler, Carolyn B.;  
Kaes, Herbert D.; Hicks, Robert F.; Williams, R. Stanley

CS Dep. Chem. Biochem., Univ. California, Los Angeles, CA, 90024-1569, USA

SO J. Am. Chem. Soc. (1989), 111(24), 8779-84  
CODEN: JACSAT; ISSN: 0002-7863

DT Journal

LA English

OS CASREACT 111:233169

L2 ANSWER 9 OF 10 CAPLUS COPYRIGHT 1999 ACS

AN 1989:48680 CAPLUS

DN 110:48680

TI Low-temperature organometallic chemical **vapor** deposition of  
platinum

AU Chen, Yea Jer; Kaes, Herbert D.; Thridandam, Hareesh; Hicks, Robert F.

CS Dep. Chem. Biochem., Univ. California, Los Angeles, CA, 90024-1569, USA

SO Appl. Phys. Lett. (1988), 53(17), 1591-2  
CODEN: APPLAB; ISSN: 0003-6951

DT Journal

LA English

L2 ANSWER 10 OF 10 CAPLUS COPYRIGHT 1999 ACS

AN 1979:575506 CAPLUS

DN 91:175506

TI Synthesis, infrared, Raman and proton NMR spectra of the tetramer:  
tetrakis[trimethyl(methylthio)platinum(IV)], [  
Pt(CH<sub>3</sub>)<sub>3</sub>SCH<sub>3</sub>]<sub>4</sub>

AU Hall, J. R.; Hirons, D. A.; Swile, G. A.

CS Dep. Chem., Univ. Queensland, Brisbane, 4067, Australia

SO J. Organomet. Chem. (1979), 174(3), 355-8  
CODEN: JORCAI; ISSN: 0022-328X

DT Journal

LA English

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FILE 'CAPLUS' ENTERED AT 09:14:32 ON 27 OCT 1999

FILE 'JAPIO' ENTERED AT 09:14:34 ON 27 OCT 1999